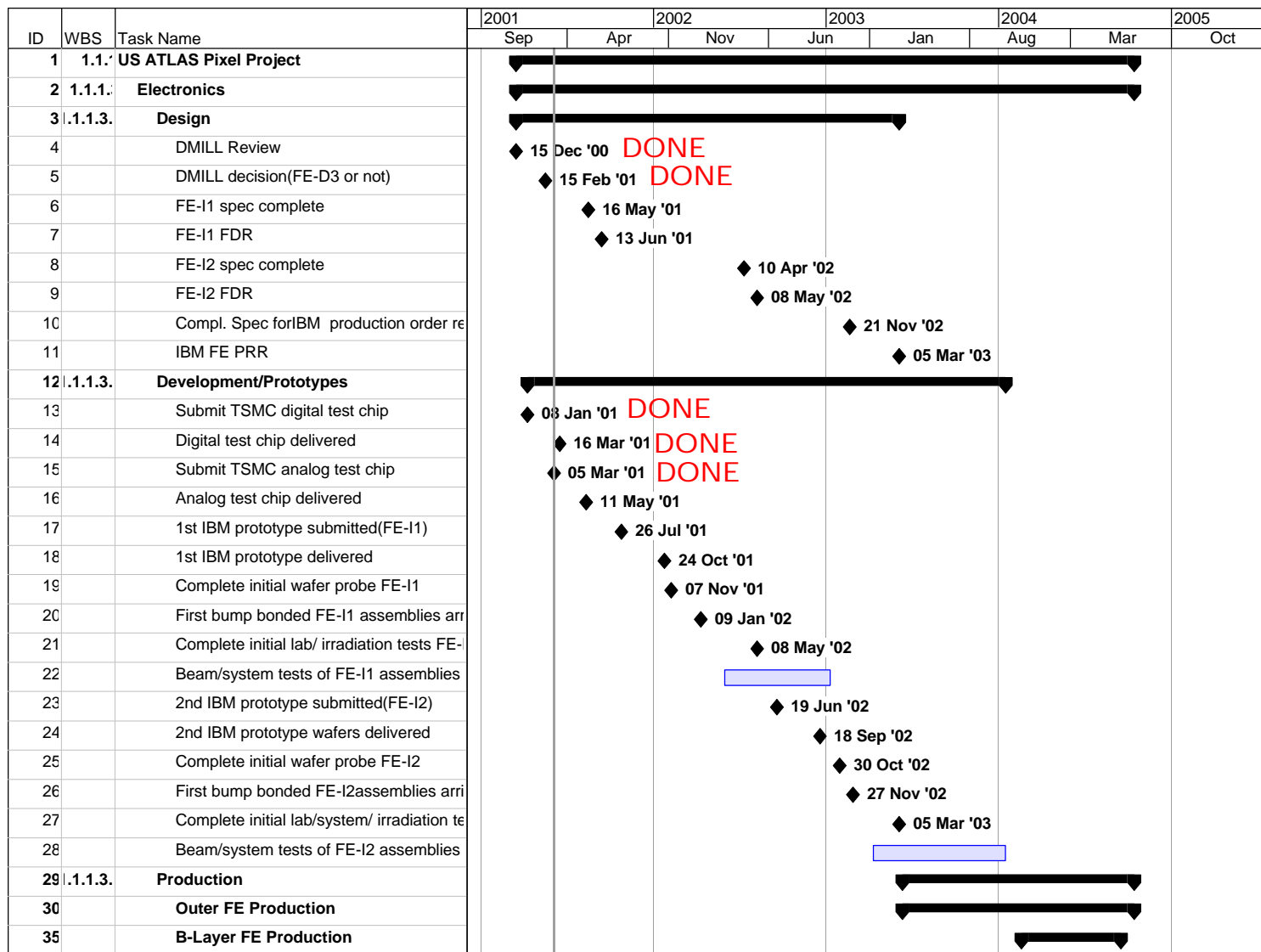


Pixel Frontend Electronics in 0.25 μ m CMOS

- Pixel → Radiation-tolerant CMOS design
CERN RD-49, FPIX for BTeV, ...
Smaller feature size has allowed design to become more conservative (*DMILL* design was space-constrained)
- Pixel FE-I Roadmap
Technology/Design developments required
Test chips
Planning and status



Plan as Presented in Pixel Baseline Review (11 '00)



Roadmap

- Develop in two technologies
Baseline: order via CERN frame contract, Backup: TSMC
- Insert test chip runs to cross-check (before full wafer run)
- Minimize layout time (Small feature size \Rightarrow extra space. Use synthesis + automated place-and-route wherever possible)
- Maximize verification time (2 000 000 transistor, mixed-mode chip)
- Submit 1st full-wafer run by end July '01

FE-I Design team

Mario Ackers - Bonn

Laurent Blanquart - Marseille

now LBL (from 28 Feb. 01)

Giacomo Comes - Bonn

Peter Denes - LBL

Kevin Einsweiler - LBL

Peter Fischer - Bonn

Ivan Peric - Bonn

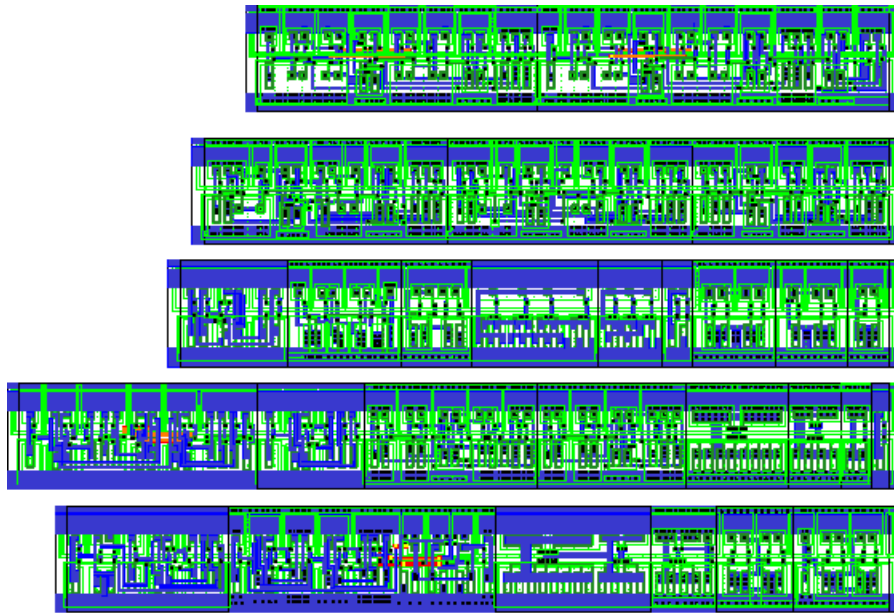
Emanuele Mandelli - LBL

Roberto Marchesini - LBL (until 16 Jan 01)

Gerrit Meddeler - LBL



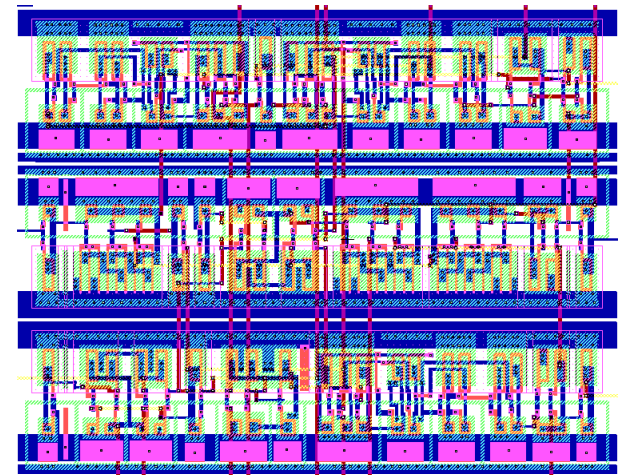
Technology / Design Developments



Mixed-mode standard cell library
(Modification of CERN / RAL
library - Bonn)

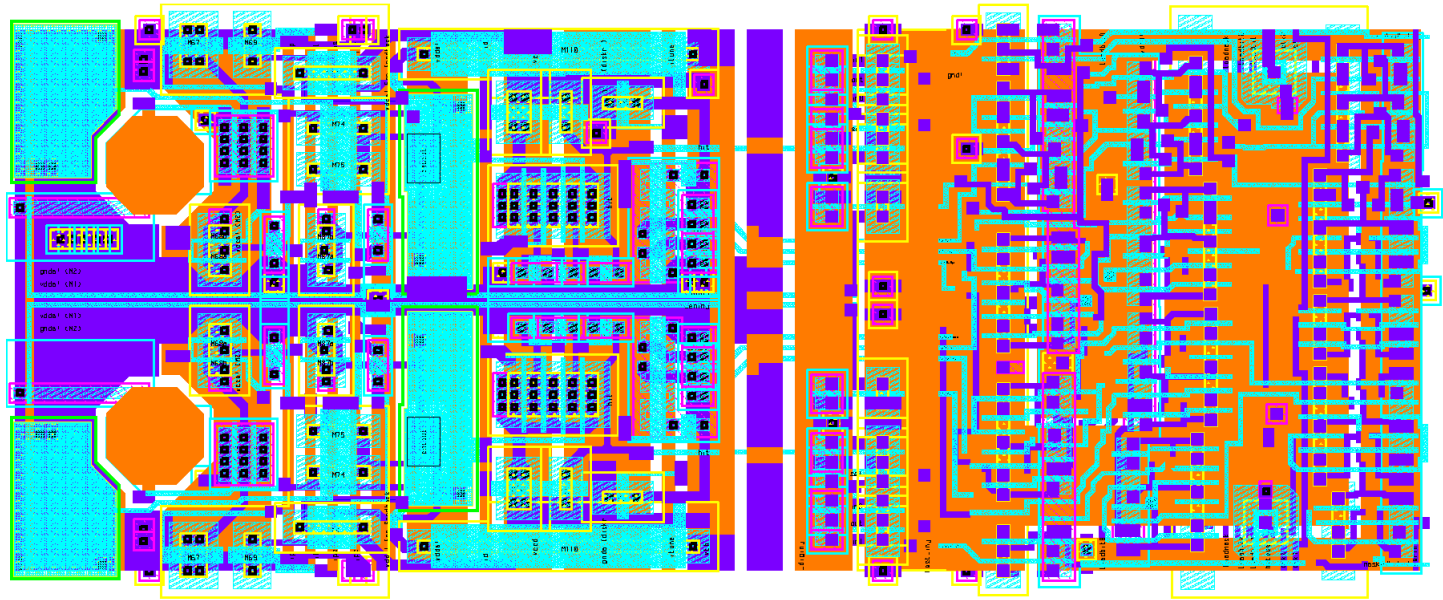
Implement Silicon Ensemble (to be
able to autoroute standard cells - LBL)

example - Pixel Logic

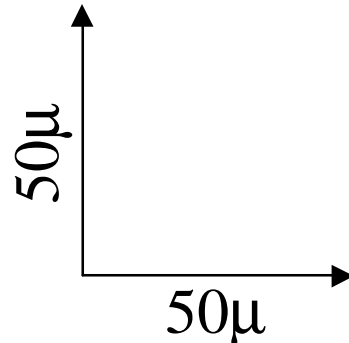
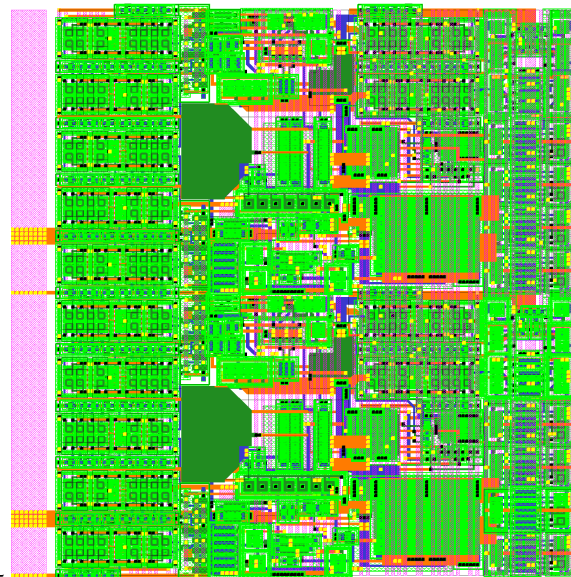


Comparative Size

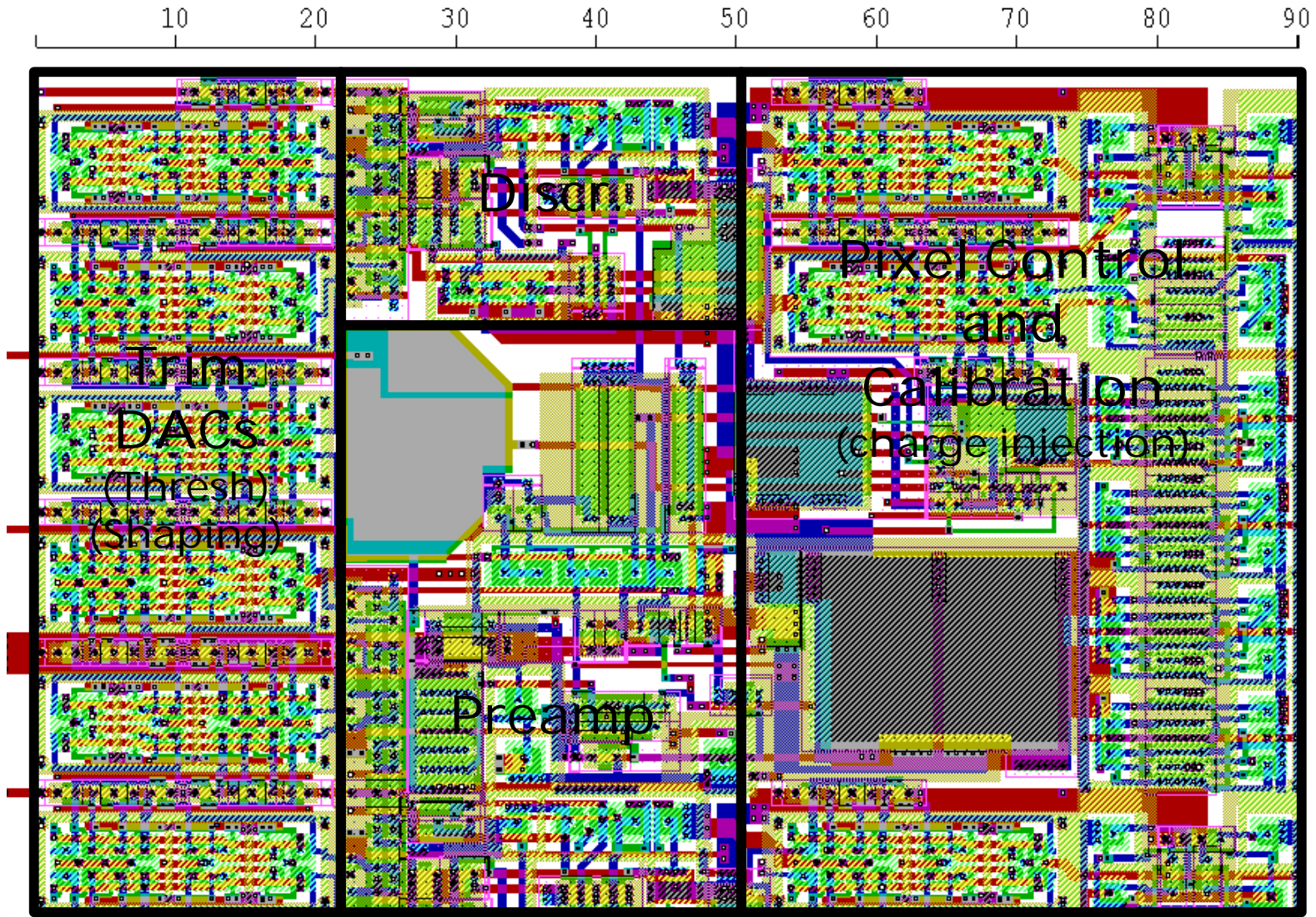
Two pixels
(analog)
in *DMILL*



Two pixels
in 0.25μ



In a Pixel

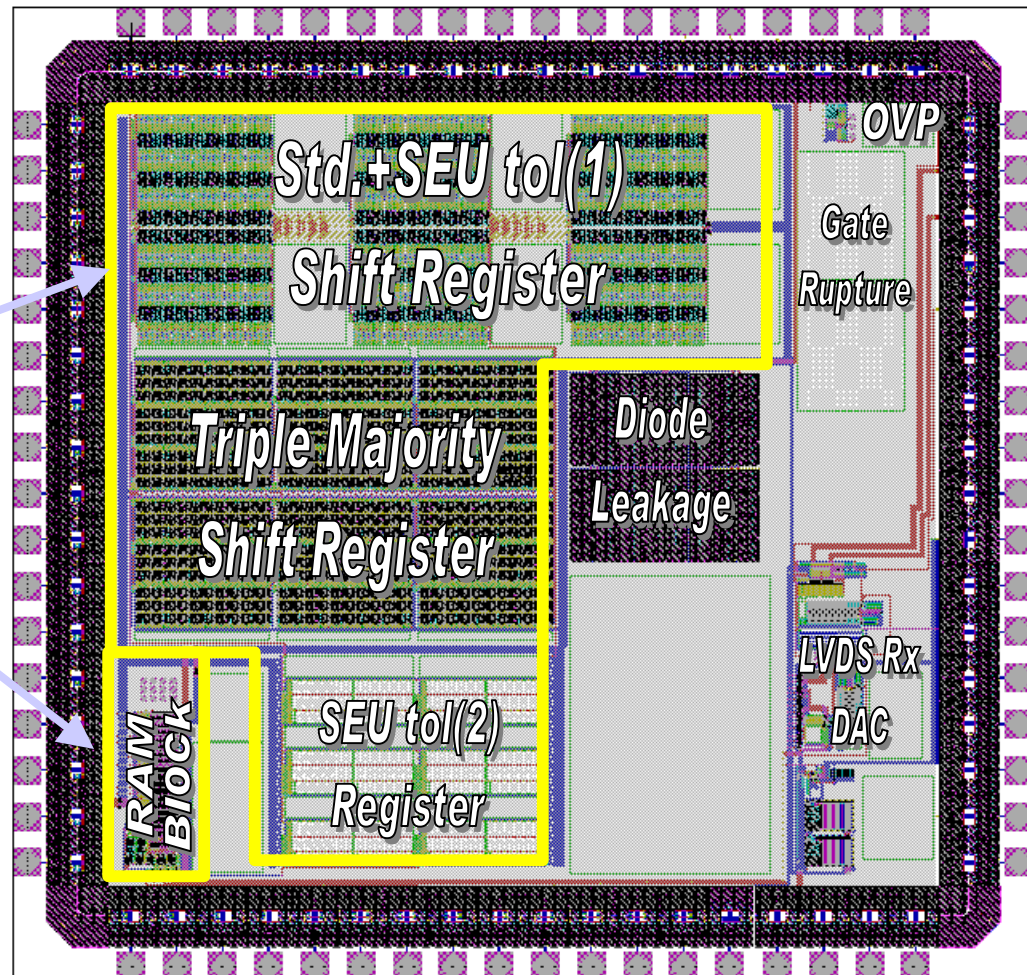


Digital Test Chip

TSMC 0.25 μ
Submitted 08 Jan '01

Structures to test SEU
sensitivity of storage registers
Pixel RAM block

Irradiate Apr '01



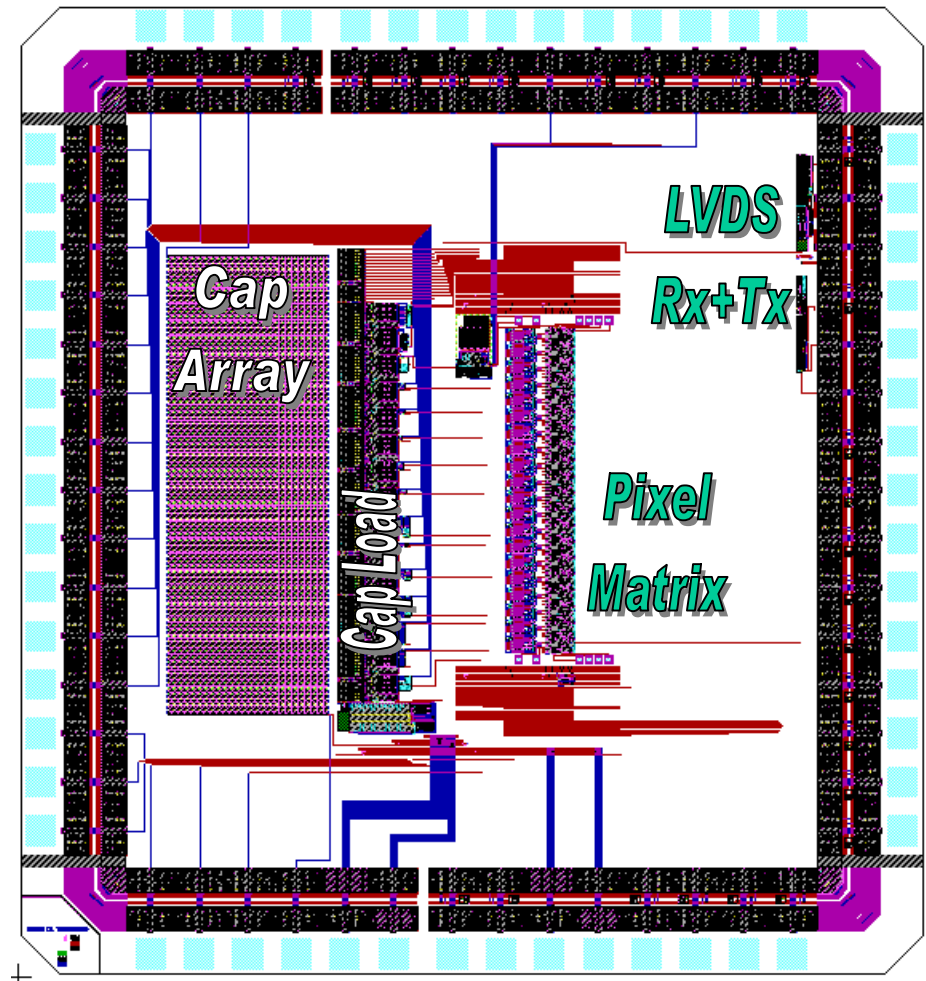
Analog Test Chip

Submitted (CERN) 28 Feb 01

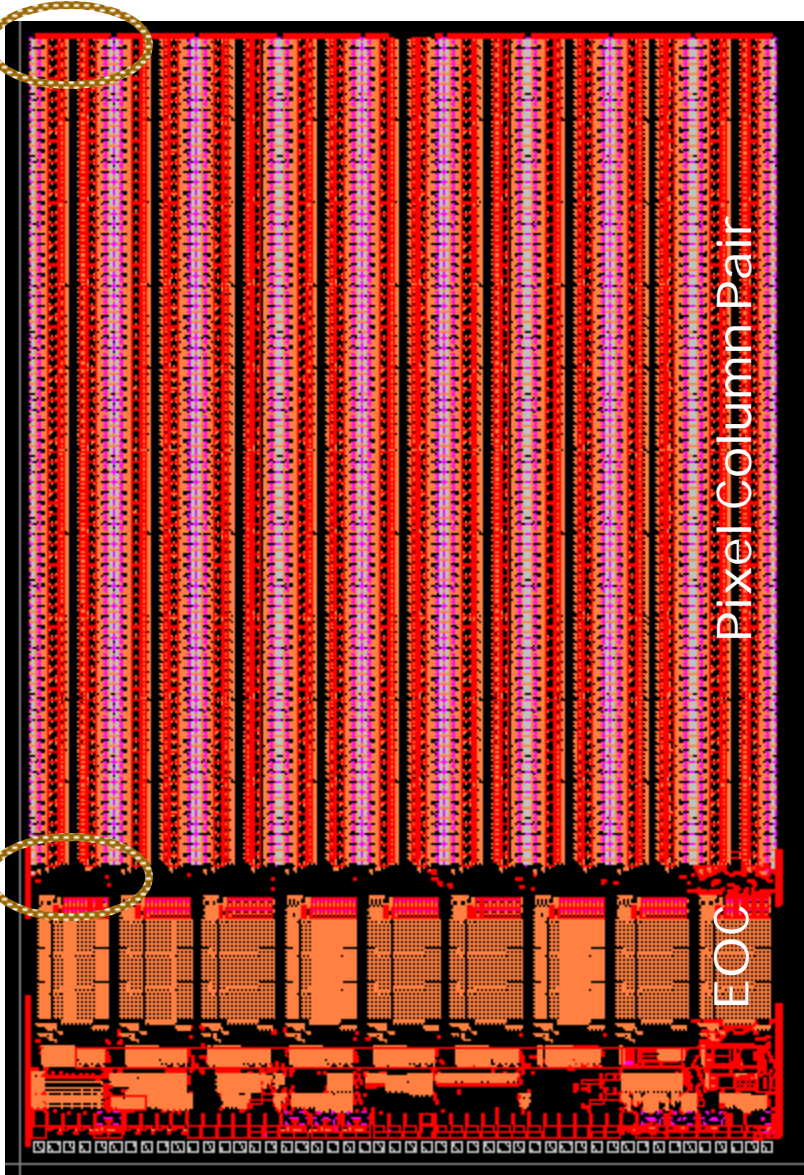
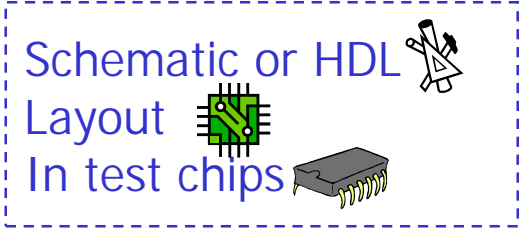
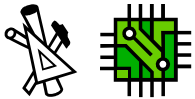
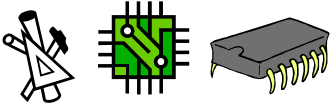
Submitted (TSMC) 6 Mar 01

Array of pixels along with
other analog functions

- Preamp and discriminator
- Trim DACs
- Main DACs
- 50 Ω output buffer
- Input capacitance test structure

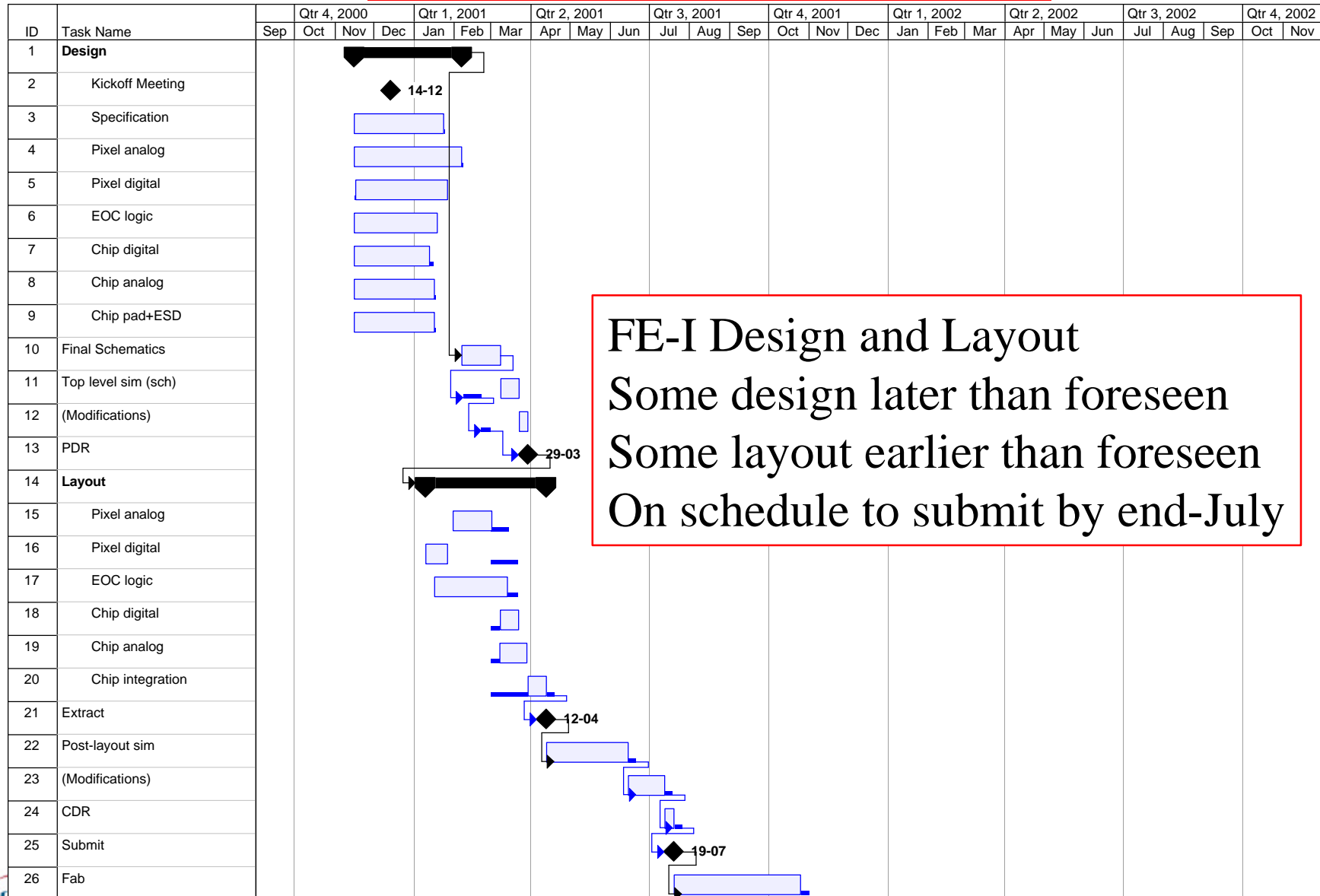


Status - Ready to Assemble Final Chip



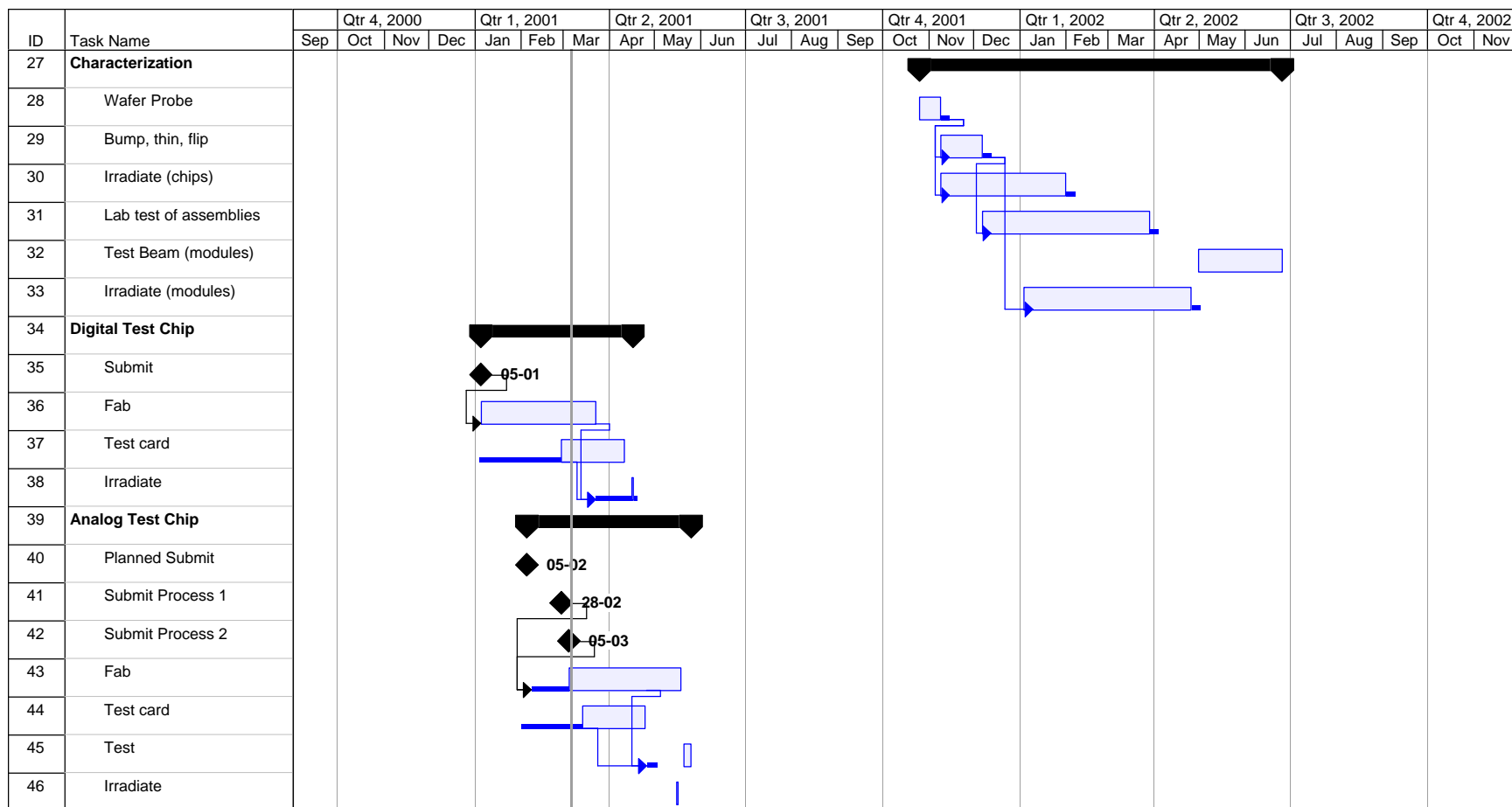
FE-D

Planning (1) - Design/Fabricate



FE-I Design and Layout
 Some design later than foreseen
 Some layout earlier than foreseen
 On schedule to submit by end-July

Planning (2) - Characterization



US ATLAS E.T.C.

WBS Number	Description	FY 96 (k\$)	FY 97 (k\$)	FY 98 (k\$)	FY 99 (k\$)	FY 00 (k\$)	FY 01 (k\$)	FY 02 (k\$)	FY 03 (k\$)	FY 04 (k\$)	FY 05 (k\$)	Total (k\$)
1.1.1.3	Electronics	0	0	0	0	0	615	621	354	26	0	1616
1.1.1.3.1	Design/Engineering	0	0	0	0	0	381	446	161	0	0	989
1.1.1.3.1.1	IC design	0	0	0	0	0	189	269	11	0	0	469
1.1.1.3.1.2	Test design	0	0	0	0	0	140	75	0	0	0	216
1.1.1.3.1.3	Systems Engineering	0	0	0	0	0	52	101	151	0	0	304
1.1.1.3.2	Development and Prototypes	0	0	0	0	0	234	133	0	0	0	367
1.1.1.3.2.1	Atmel/DMILL prototypes	0	0	0	0	0	130	0	0	0	0	130
1.1.1.3.2.2	Honeywell	0	0	0	0	0	10	0	0	0	0	10
1.1.1.3.2.3	0.25 Micron	0	0	0	0	0	0	54	0	0	0	54
1.1.1.3.2.4	Test	0	0	0	0	0	94	79	0	0	0	173
1.1.1.3.3	Production	0	0	0	0	0	0	42	193	26	0	261
1.1.1.3.3.1	Front-end ICs	0	0	0	0	0	0	19	140	26	0	185
1.1.1.3.3.2	Optoelectronics	0	0	0	0	0	0	23	53	0	0	76

